

TSMC-01-848



December 12, 2003

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/666,355 09/19/03 |

Jyh-Shiou Hsu et al.

A NOVEL METHOD TO CONTROL SPACER
WIDTH

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on December 19, 2003.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

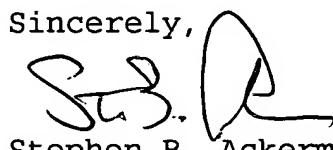
A handwritten signature in black ink, appearing to read "Stephen B. Ackerman", followed by a date line with "12/19/03" written in a stylized, cursive font.

U.S. Patent 6,268,253 to Yu, "Forming a Removable Spacer of Uniform Width on Sidewalls of a Gate of a Field Effect Transistor During a Differential Rapid Thermal Anneal Process," describes a removable spacer process.

U.S. Patent 5,899,722 to Huang, "Method of Forming Dual Spacer for Self Aligned Contact Integration," describes a double spacer process.

U.S. Patent 5,879,998 to Krivokapic, "Adaptively Controlled, Self-Aligned, Short Channel Device and Method for Manufacturing Same," describes a short channel device with double spacers.

Sincerely,



Stephen B. Ackerman,
Reg. No. 37761



Form PTO-1449

**E INFORMATION DISCLOSURE CITATION
IN AN APPLICATION**

Doctor Number (Optional)

Agavean Man

TSMC - 01-848 10/666, 355.

Applicant
Jyh-Shiou Hsu et al.

Firing Date 09/19/03 Grade Art Unit

U. S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

OTHER DOCUMENTS (Including Author, Title, Date, Portion and Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.